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ABSTRACT

0036        A method and system for detecting contaminants during a semiconductor fabrication operation involving a semiconductor-coating device. A beam of laser light is generated from a laser light source attached to at least one coater cup associated with the semiconductor coating device utilized in the semiconductor fabrication operation. The semiconductor fabrication operation may then be automatically terminated in response to detecting the contaminants utilizing the beam of laser light. The laser light source may be configured as one or more laser generators and/or laser detectors. Such a method and system can thus be implemented to detect photoresist (PR) dust, which is scattered during wafer coating operations.

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